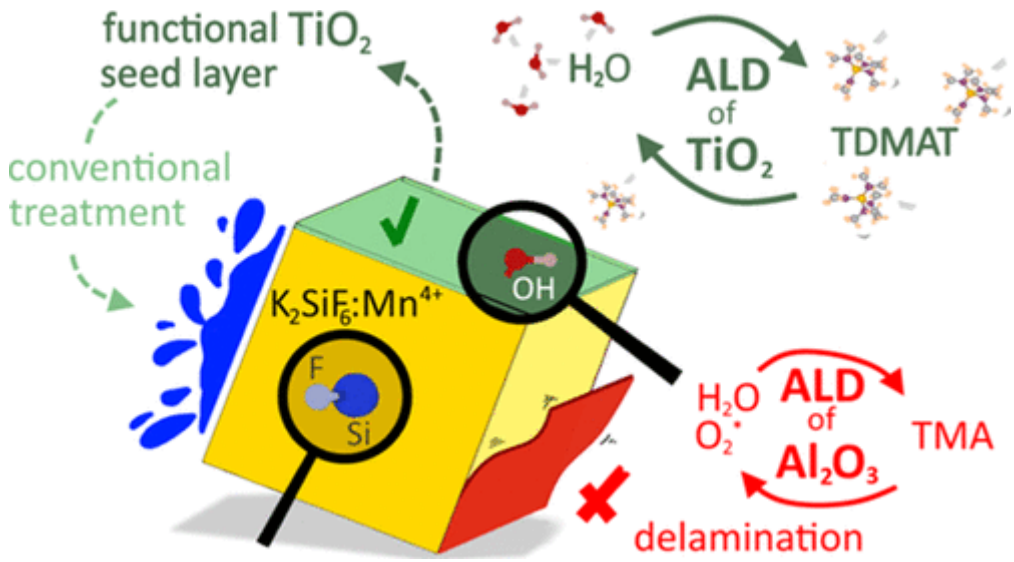
functional TiO_2
seed layer
conventional
treatment
H_2O
ALD
of
TiO_2
TDMAT
$K_2SiF_6:Mn^{4+}$
OH
F
Si
H_2O
$O_2^{\bullet}$
ALD
of
Al_2O_3
TMA
delamination